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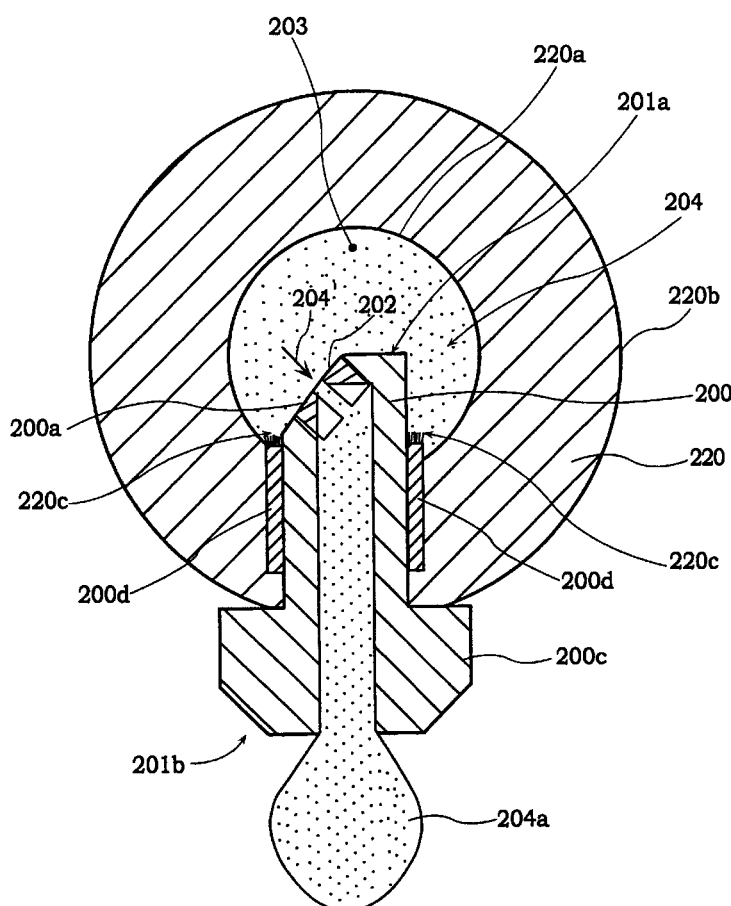
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(54) Title: DRIP MANIFOLD FOR UNIFORM CHEMICAL DELIVERY



(57) Abstract: A drip manifold (220) having drip nozzles (200) configured to form controlled droplets (204a) is provided for use in wafer cleaning systems (120). The drip manifold (220) includes a plurality of drip nozzles (200) that are secured to the drip manifold (220). Each of the plurality of drip nozzles (200) has a passage (205) defined between a first end (201a) and a second end (201b). A sapphire orifice (202) is defined within the passage (205) and is located at the first end (201a) of the drip nozzle (200). The sapphire orifice (202) is angled to produce a fluid stream that is reflected within the passage (205) and toward the second end (201b) to form one or more uniform drops (204a) over a brush (300).

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